

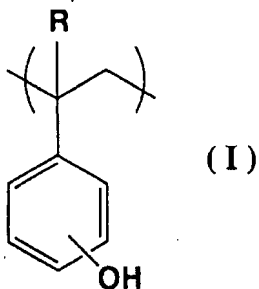
LISTING OF CLAIMS (No amendments have been made)

1. (Previously presented) A positive resist composition, comprising a resin component (A) which contains acid dissociable, dissolution inhibiting groups, and exhibits increased alkali solubility under action of acid, and an acid generator component (B) that generates acid on exposure, wherein

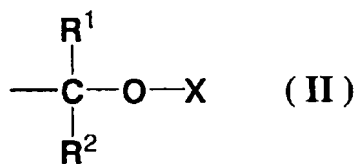
said resin component (A) is a polymer comprising structural units (a1) represented by a general formula (I) shown below, and a portion of hydroxyl groups of said structural units (a1) are protected by substituting hydrogen atoms of said hydroxyl groups with acid dissociable, dissolution inhibiting groups represented by a general formula (II) shown below, wherein

said polymer of said component (A) further comprises structural units (a2) represented by a general formula (III) shown below; and wherein

said component (A) is a mixture of a polymer, which comprises said structural units (a1), and in which a portion of hydroxyl groups of said structural units (a1) are protected with said acid dissociable, dissolution inhibiting groups, and a copolymer, which comprises said structural units (a1) and said structural units (a2), and in which a portion of hydroxyl groups of said structural units (a1) are protected with said acid dissociable, dissolution inhibiting groups.



(wherein, R represents a hydrogen atom or a methyl group)



(wherein, R¹ represents an alkyl group of 1 to 5 carbon atoms, R² represents an alkyl group of 1 to 5 carbon atoms or a hydrogen atom, and X represents an aliphatic polycyclic group or an aromatic polycyclic hydrocarbon group).